Quantum perspectives in computing, sensing, communication, and metrology **Edoardo Charbon** EPFL, Lausanne, Switzerland

Aknowledgements

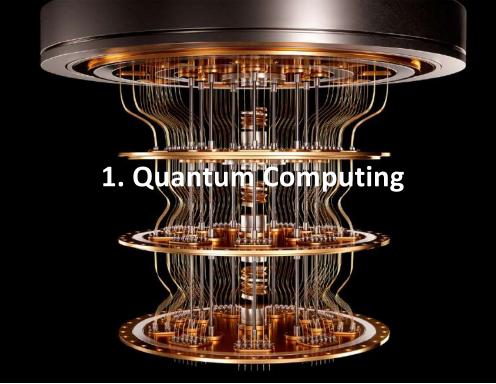
Simone Frasca Pascal 't Hart Jiang Gong Harald Homulle Andrea Ruffino Yatao Peng M. Fernando Gonzalez-Zalba Fabio Sebastiano Masoud Babaie Daniele Faccio Andrew Dzurak

Outline

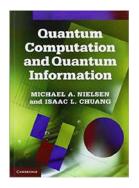
- Quantum computing (2 periods)
- 2. Cryogenic electronics (2 periods)

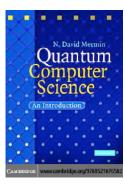
Available in a future class:

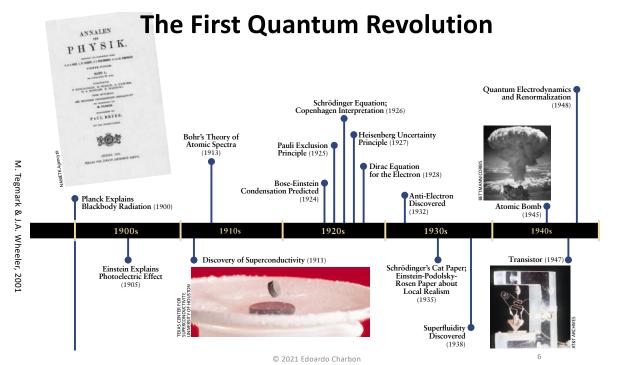
- 3. Quantum algorithms (2 periods)
- Quantum imaging and communications (1 period)
- 5. Quantum metrology (2 periods)



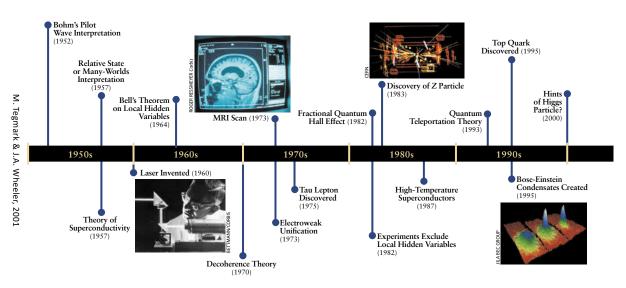
Suggested Reading







The First Quantum Revolution

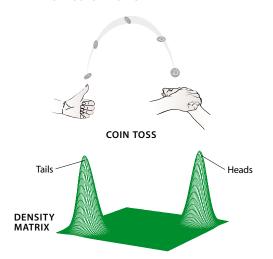


Weird Quantum Properties:

Superposition & Entanglement

Superposition

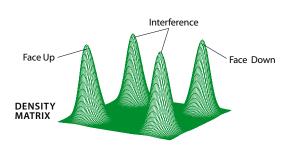
CLASSICAL UNCERTAINTY



QUANTUM UNCERTAINTY



COHERENT SUPERPOSITION



Coherence / Decoherence

Entanglement

<u>Definition:</u> two particles are entangled if the quantum state of one particle cannot be described independently from the quantum state of the other particle.

<u>Intuition:</u> measuring the quantum state of one particle implies knowledge of the quantum state (e.g. momentum, spin, polarization, etc.) of the other entangled particle using the same projection.

The Second Quantum Revolution

• Spearheaded by many, in primis Richard Feynman

Proposal to use of entanglement and superposition for computation

• Fundamentals and theory developed in the 1980-2000s

There is plenty of space at the bottom

- Richard Feynman



The Promise of Quantum Computing



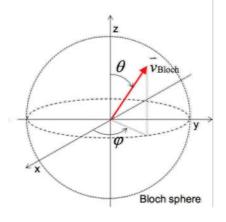
Energy
Room-temperature superconductivity





Source: L. Vandersypen, ISSCC 2017

Quantum Bit (Qubit)



$$|\psi\rangle = \alpha_0 |0\rangle + \alpha_1 |1\rangle$$

- Superposition
- Entanglement

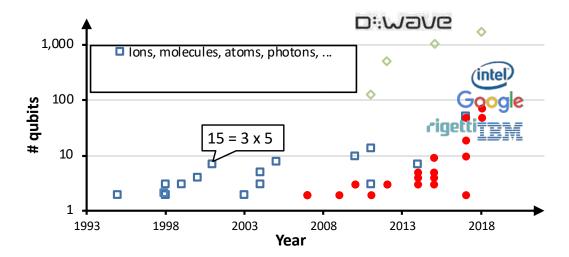
The Power of Superposition

1 qubit	2 states
2 qubits	4 states
·	
N qubits	2 ^N states

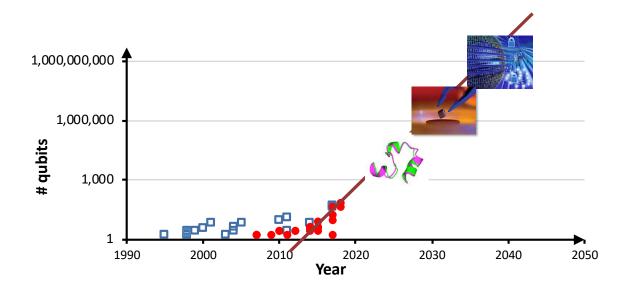
40 qubits: 10¹² parallel operations

300 qubits: more than the atoms in the universe

State-of-the-Art



How Far Are We from Something Useful?



Quantum Supremacy or Quantum Advantage

Quantum supremacy is the potential ability of quantum computing devices to solve problems that classical computers practically cannot.

[Wikipedia]

Google claims to have reached quantum supremacy (Financial Times)

Report on a an accepted paper to a peer-reviewed publication

Solid-state Qubit Implementations Today

- Based on superconducting qubits
- First multi-qubit chips announced
- Freely available qubits on line

72-qubit chip announced

Total 22 qui foote

Total 22 qui foote

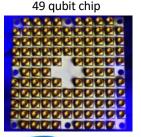
Total 32 qui foote

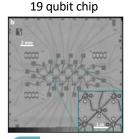
T

Source: Tristan Meunier

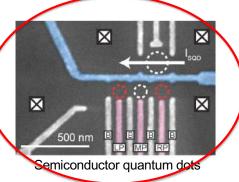
16 Qubits online version

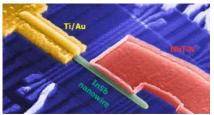
50 qubit chip announced





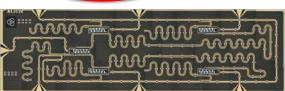
Solid-state Qubit Implementations Today

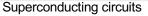


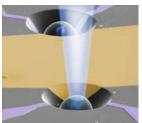


Semiconductor-superconductor hybrids







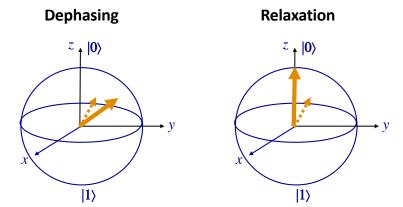


Impurities in diamond or silicon

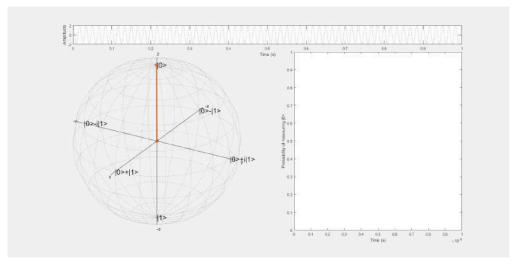
ource: L. Vandersypen, 2017

Qubits are Fragile

- Environment can cause decoherence due to dephasing and relaxation
- Fidelity



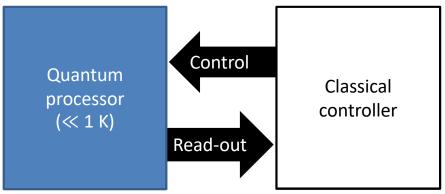
Qubit Transition from |0> to |1>



© Jeroen van Dijk

Interfacing Qubits with Classical World

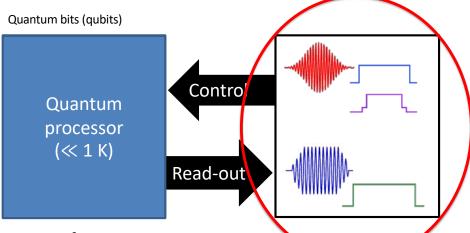
Quantum bits (qubits)



• Carrier frequency: 100 MHz – 15 GHz, 70 GHz

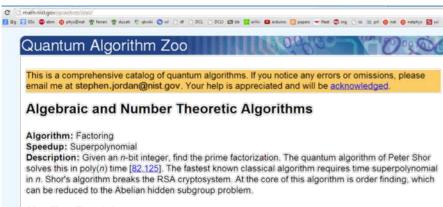
Pulses: 10 – 100 ns

Interfacing Qubits with Classical World



- Carrier frequency: 100 MHz 15 GNz, 70 GHz
- Pulses: 10 100 ns
- Readout techniques for spin qubits: ESR, EDSR

Status of Quantum Algorithms

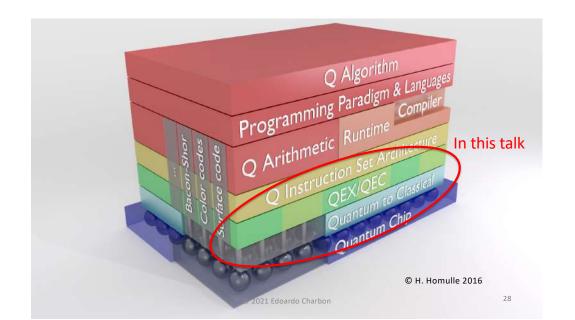


Algorithm: Discrete-log Speedup: Superpolynomial

Description: We are given three n-bit numbers a, b, and N, with the promise that $b = a^s \mod N$ for some s. The task is to find s. As shown by Shor [82], this can be achieved on a quantum computer in poly(n) time. The fastest known classical algorithm requires time superpolynomial in n. By similar

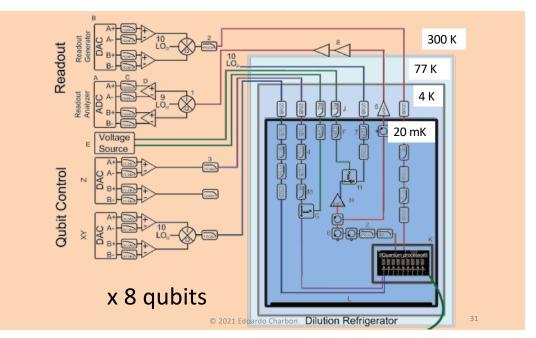
~50 algorithms with quantum speedup, but most people know 2.

Quantum Computing Stack



Quantum Computer Architecture

A Real-life Quantum Computer



Today's Solution

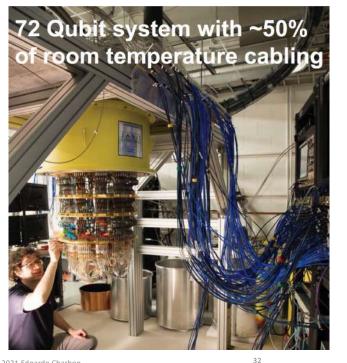
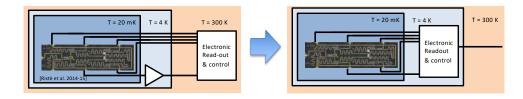


Image: Google Bristlecone. Taken from: J.C. Bardin et al., "An Introduction to Quantum Computing for RFIC Engineers", RFIC Symposium 2019

Our Proposed Solution

Proposed solution

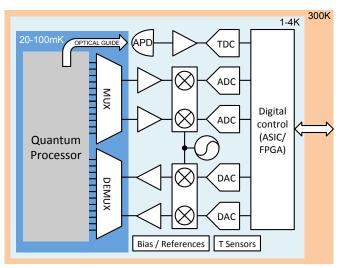
- Electronics at 4 K
- Only connections to 4 K to 20 mK are needed



Ultimate solution

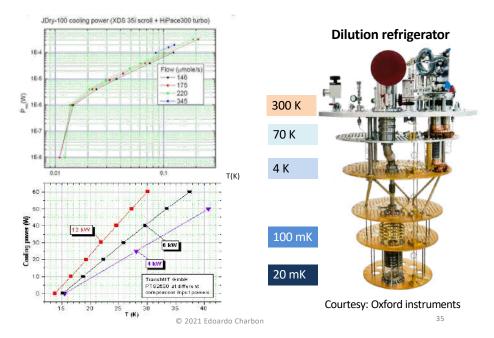
- Qubits at 4 K
- Monolithic integration

Electronic Readout & Control



E. Charbon et al., IEDM 2016

Cooling Power Issue



Scalability Issue

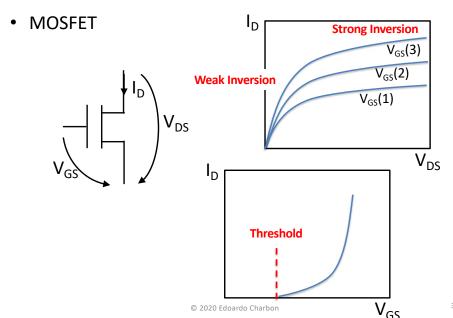
•	Noise budget	.< 0.1nV/√Hz
•	Power budget (for scalability)	<< 2mW/qubi
•	Physical dimensions (for scalability)	30nm
•	Bandwidth (for multiplexing)	1-12GHz
•	Kick-back avoidance	

2. Cryogenic Electronics

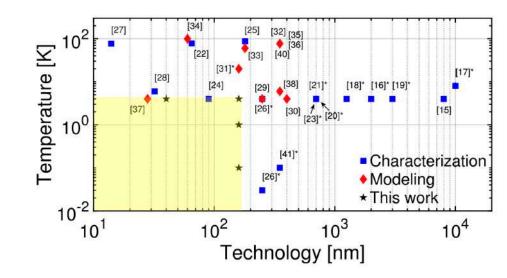
Transistor Modeling at Deep Cryogenic

Temperatures

CMOS Modeling: Important Parameters



CMOS Modeling: History



R.M. Incandela et al., ESSDERC 2017 R.M. Incandela et al., J. of EDS 2018

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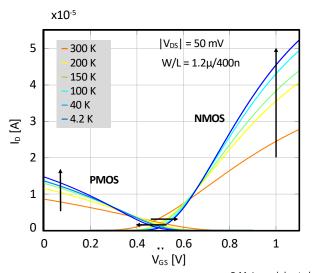
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R.M. Incandela et al., J. of EDS 2018

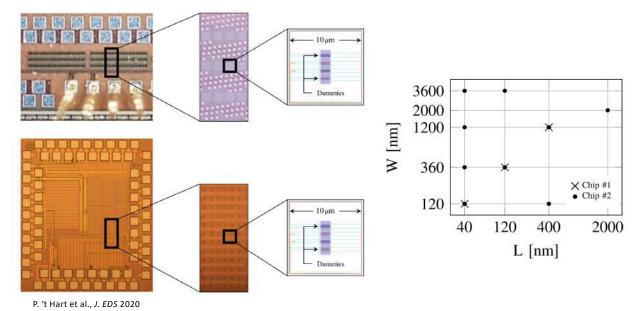
What Happens to CMOS at Cryo?



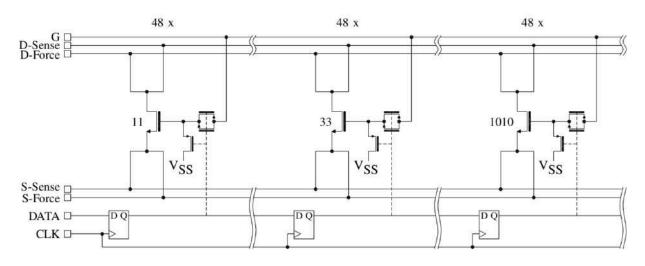
- Threshold voltage increases significantly
- A current kink may appear
- Mismatch in passives and actives is more prominent
- The substrate becomes practically floating
- The SS is higher but it saturates around 1K
- Leakage drastically reduces

R.M. Incandela et al., ESSDERC 2017 R.M. Incandela et al., J. of EDS 2018

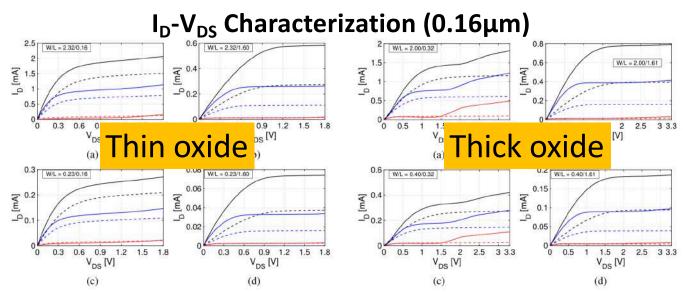
How to Characterize MOS Transistors?



CMOS Characterization in Practice



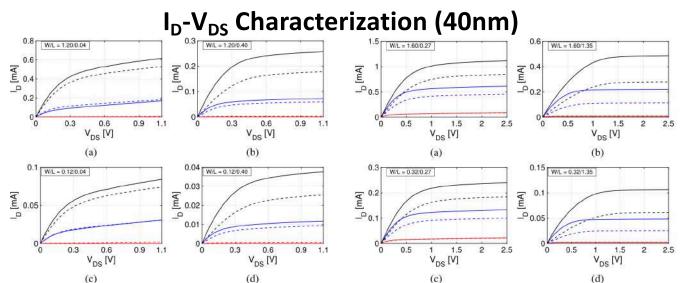
P. 't Hart et al., J. EDS 2020



R.M. Incandela et al., J. of EDS 2018

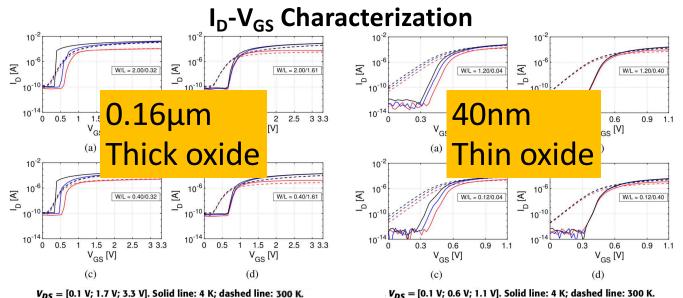
V_{GS} = [0.68 V; 1.24 V; 1.8 V]. Solid line: 4 K; dashed line: 300 K.

V_{GS} = [1.05 V; 2.17 V; 3.3 V]. Solid line: 4 K; dashed line: 300 K.



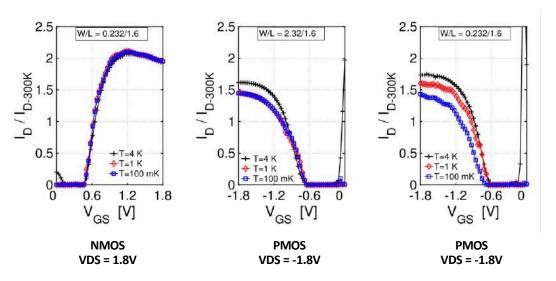
V_{GS} = [0.43 V; 0.76 V; 1.1 V]. Solid line: 4 K; dashed line: 300 K.

V_{GS} = [0.85 V; 1.68 V; 2.5 V]. Solid line: 4 K; dashed line: 300 K.



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I_D-V_{GS} Characterization in Sub-K Regimes

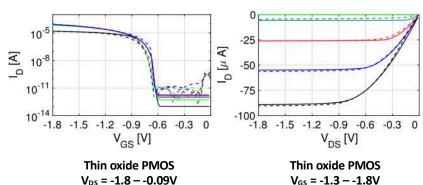


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CMOS Modeling

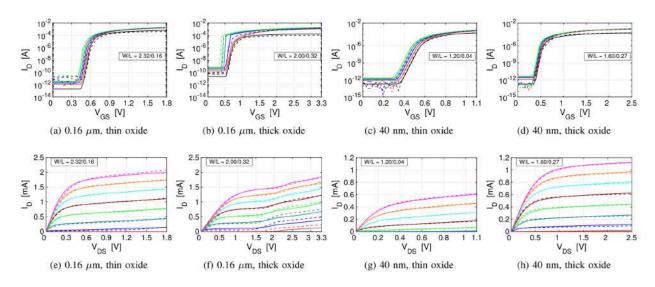
	MOS11 pa	arameters for	0.16-μm CM	OS	
BETSQR	VFBR	THESRR	SDIBLO	ALPR	KOR
THESATR	THERR	A1R	A2R	A3R	
	PSP pa	rameters for	40-nm CMOS		
FACTUO	DELVTO	THEMUO	THESATO	RSW1	CFL
ALPL	MUEO	FBET1			





•

CMOS Modeling



Sub-threshold Slope (SS)

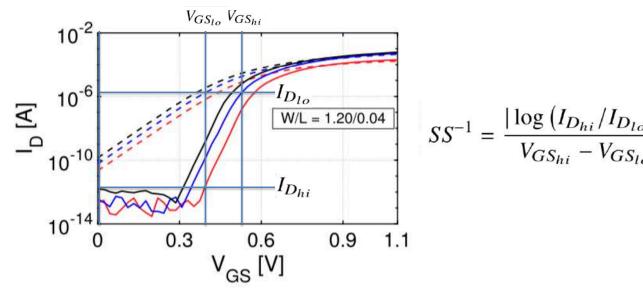
$$SS = \ln(10) \frac{kT}{q} \left(1 + \frac{C_d}{C_{ox}} \right)$$

 C_d = depletion layer capacitance C_{ox} = gate oxide capacitance

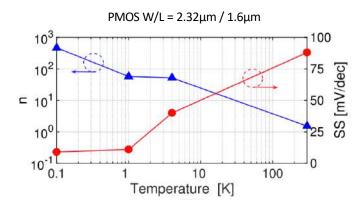
$$SS = \ln(10) \frac{kT}{q} \sim 60 \text{mV/dec}$$

$$C_d = 0$$
; $C_{ox} \rightarrow$: thermionic limit

Sub-threshold Slope Characterization(SS)

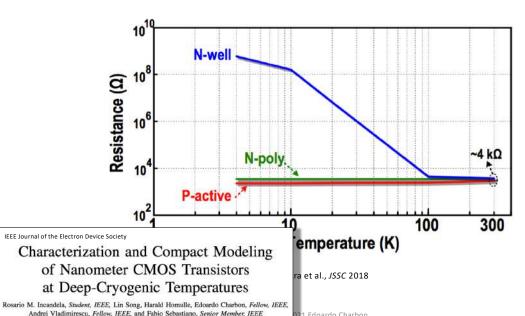


Sub-threshold Slope (SS)



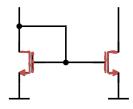
R.M. Incandela et al., ESSDERC 2017 R.M. Incandela et al., J. of EDS 2018

Substrate Resistivity



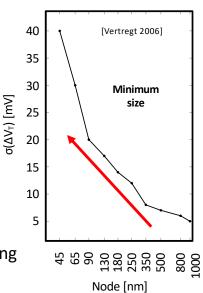
Mismatch Modeling at Cryo

Subthreshold Current Mismatch: Why Do We Care?



- Impacts performance of:
 - ADC/DAC
 - Differential pairs
 - SRAM

Worsens with technology scaling



Subthreshold Current Model

$$I_D = I_0 e^{(V_{GS} - V_{TH})/SS}$$

Taylor expansion is impractical at cryo due to the instability of ID and the exponential nature of it.

Solve wrt $log(I_D)$

$$\log{(I_D)} \propto \frac{1}{\ln(10)} \frac{V_{GS} - V_{TH}}{SS}.$$

Taylor expansion on V_{TH} and SS

$$\Delta \log (I_D) = \frac{1}{\ln(10)} \left(-\frac{1}{SS} \Delta V_{TH} - \frac{(V_{GS} - V_{TH})}{SS} \frac{\Delta SS}{SS} \right)$$

Subthreshold Current Model

$$\sigma_{\Delta \log I_D}^2 = \frac{1}{\ln(10)^2} \left[\left(\frac{\sigma_{\Delta V_{TH}}}{\overline{SS}} \right)^2 + \left(\frac{V_{GS} - V_{TH}}{\overline{SS}} \frac{\sigma_{\Delta SS}}{\overline{SS}} \right)^2 + 2 \frac{(V_{GS} - V_{TH})}{\overline{SS}^3} \sigma_{\Delta V_{TH}} \sigma_{\Delta SS} \rho_{\Delta V_{TH}, \Delta SS} \right].$$
 (5)

The correlation factor ρ between $V_{\rm TH}$ and SS is generally negligible at 300K, 100K, and also at cryogenic temperatures.

Croon Model

$$\sigma_{\Delta I_D/I_D}^2 = \ln(10)^2 \sigma_{\Delta \log I_D}^2$$

$$\sigma_{\Delta \log I_D}^2 = \frac{1}{\ln(10)^2} \left[\sigma_{\Delta\beta/\beta}^2 + \left(\frac{\bar{g}_m}{\bar{I}_D} \right)^2 \sigma_{\Delta V_{TH}}^2 \right], \tag{7}$$

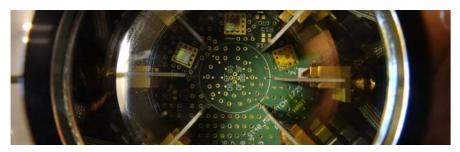
Pelgrom Scaling Law

$$\sigma_{\Delta V_{TH}} = \frac{A_{VT}}{\sqrt{WL}}$$
 $\sigma_{\Delta\beta/\beta} = \frac{A_{\beta}}{\sqrt{WL}}$ $\sigma_{\Delta SS/SS} = \frac{A_{SS}}{\sqrt{WL}}$

 A_{VT} : area scaling parameter for $V_{\rm T}$ A_{β} : area scaling parameter for β A_{SS} : area scaling parameter for SS

W, L: transistor geometry parameters

How to Characterize Mismatch?



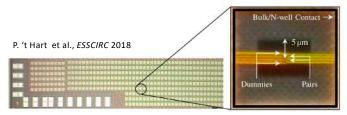
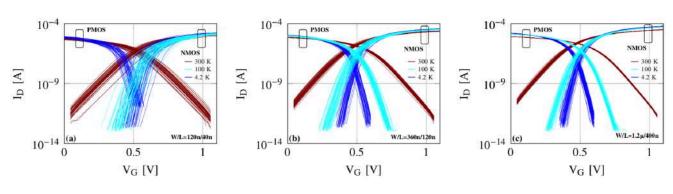


Fig. 1. Die micrograph (*left*) with close-up of a $W/L = 1.2\,\mu\text{m}/0.4\,\mu\text{m}$ matched pair (*right*).

Mismatch Measurements



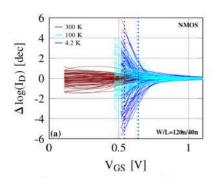
48 devices tested

 $|V_{\rm DS}|$ = 50mV, $V_{\rm S}$ =0V (NMOS)

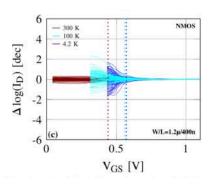
 $|V_{\rm DS}|$ = 50mV, $V_{\rm S}$ =1.1V (PMOS)

P. 't Hart et al., J. of EDS 2020

Mismatch Measurements (2)



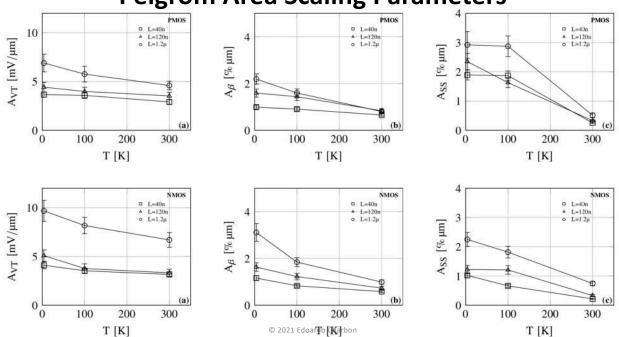
6 - 300 K NMOS NMOS - 42 K NMO



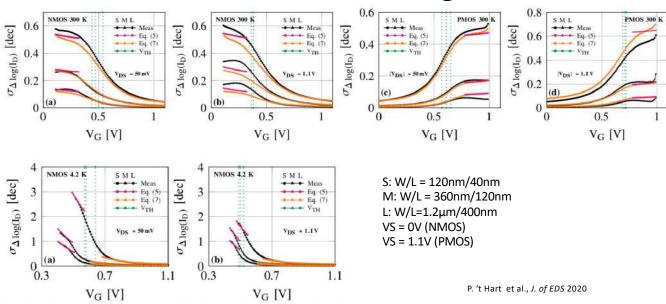
72 device pairs tested V_{TH} in dashed lines $|V_{\rm DS}|$ = 50mV

P. 't Hart et al., J. of EDS 2020

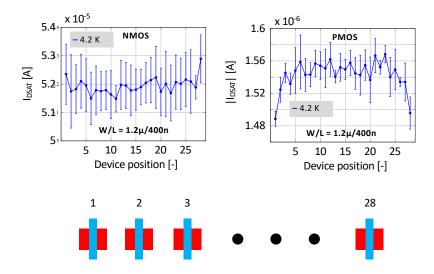
Pelgrom Area Scaling Parameters



Mismatch Modeling



Position Dependence



Summary on Threshold Mismatch

Cryo-CMOS: mismatch follows Pelgrom and Croon models

Fixed V_{GS} biasing → matching deteriorates up to 10x

• Fixed G_m/I_D biasing \rightarrow matching deteriorates "only" 1.1x

Digital Modeling at Cryo

Lowerbound in Digital Design

$$V_{DD,min} \approx 2 \frac{kT}{q} \ln(2) = 36 \text{mV}$$

CMOS circuits operate in subthreshold wherever this equation holds

$$I_{DS} = I_0 \frac{W}{L} e^{\frac{V_{GS} - V_{TH}}{nv_t}} \left(1 - e^{\frac{-V_{DS}}{v_t}} \right); \ I_0 = \mu_0 C_{ox} \frac{W}{L} (n-1) v_t^2,$$

n is the sub-threshold slope (SS) factor and $v_t = kT/q$,

The net effect in sub-threshold regimes is a decrease of leakage currents by orders of magnitude, implying a significant increase in the I_{ON}/I_{OFF} ratio

Lowerbound in Digital Design

Assuming an ideal SS factor n = 1, at 4.2 K, according to well established room temperature models, one could theoretically achieve $V_{DD,min} \approx 2 \ln(2) v_t = 0.48 \text{mV}$.

However, at 4.2 K the consensus is that $n\approx34.9$. Thus, this fundamental limit is actually VDD, $min\approx2.47$ mV. Additional non-idealities include reverse short-channel effect (RSCE) and inverse narrow-width effect (INWE).

Both effects substantially modulate the threshold voltage.

Latchup

Latch-up has been found to be unpredictable in deep-cryogenic operation. Latch-up immunity typically improves at temperatures lower than RT, thanks to lower well and substrate resistance and to higher base-emitter voltages and lower current gain of parasitic bipolar transistors. However, shallow level impact ionization (SLII), a mechanism for carrier generation, emerges below 50 K

Recommendations

- A)create extensive substrate contacts and well-taps, so as to minimize the chance of latch-up at 4.2 K;
- B) resize the transistors, so as to reduce INWE and thus maximize V_{TH} modulation;
- C) add secondary power rails to enable forward back-biasing, so as to compensate for an increase of V_{TH} at 4.2, in addition use low- V_{TH} transistors;
- D)minimize the length of transistors (in contrast to conventional RT subthreshold standard cell design, where the opposite is generally done);
- E) when useful, make the layout aware of mismatch by increasing the overall height of the cells.

Summary of Issues 300K -> 0.1K

- Threshold voltage increases significantly
- A current kink may appear
- Mismatch in passives and actives is more prominent
- The substrate becomes practically floating
- The SS is higher but it saturates around 1K
- Leakage drastically reduces

Trends and Predictions

- How will devices perform in 5 years at 77K?
- How will FinFETs/nanowire FET behave at 77K (Lg<20nm)
- Will ballistic transport affect these devices?
- How different will optimization be at 77K?
- Is there a way to decrease V_T?

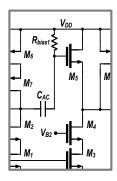
High-Level Modeling at Cryo

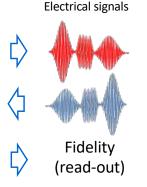
High-Level Modeling: SPINE (SPIN Emulator)

Objectives:

- Enable co-design qubit/electronics
- Derive specifications for Horse Ridge and other components
- Minimize power to achieve wanted fidelity

Circuit simulator



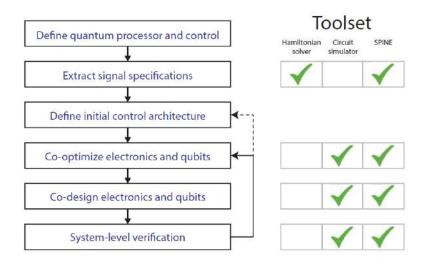


Qubit simulator (Hamiltonian)





SPINE



J. Van Dijk et al., DATE 2018

SPINE

• Microwave Carrier: **Keysight E8267D**

22.4 kHz resolution 1 mHz

- \mathcal{L} (1 MHz) = -106 dBc/Hz >15 dB better

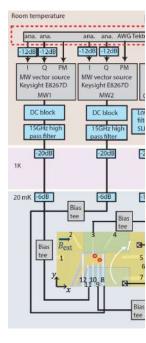
 $-S_n = 7.12 \text{ nV/VHz}$ 63 nV/VHz

 \rightarrow > 20 dB attenuation

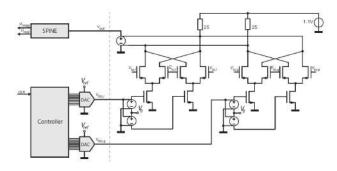
Microwave Envelope: Tektronix 5014C

8-bit resolution
 14-bit
 140 MS/s
 3.56 ns_{rms}
 40 dB SNR
 14-bit
 1.2 GS/s
 5.0 ps_{rms}
 better

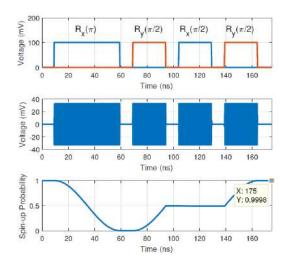
With SPINE we checked that these specs are enough



SPINE



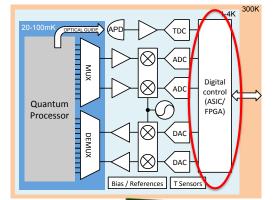
- Example of full simulation:
 - Sequence of rotations
 - Resulting RF signals
 - Qubit response, in terms of spin-up probability
- This involves spin emulation, M/S simulation, RF simulation



J. Van Dijk et al., DATE 2018

Cryogenic Reconfigurable Hardware

Cryo-FPGAs





Cryo-FPGAs

CryoCMOS Hardware Technology A Classical Infrastructure for a Scalable Quantum Computer

ACM Frontiers in Computing, Como 2016

Harald Homulle¹, Stefan Visser¹, Bishnu Patra¹, Giorgio Ferrari², Enrico Prati³, Carmen G. Almudéver¹, Koen Bertels¹, Fabio Sebastiano¹, Edoardo Charbon¹

¹QuTech, Delft University of Technology, Delft, The Netherlands

²Politecnico di Milano, Milano, Italy, ³Consiglio Nazionale delle Ricerche, Milano, Italy {h.a.r.homulle, f.sebastiano, e.charbon}@tudelft.nl



FPGA functionality

- All FPGA components are working in the cryogenic environment down to 4K
- · No modifications required

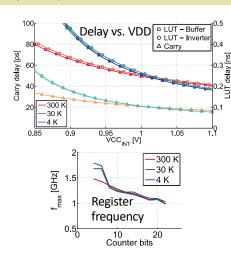
Component	Functional	Behavior
IOs	✓	
LVDS	\checkmark	
LUTs	✓	Delay change < 5%
CARRY4	\checkmark	Delay change < 2%
BRAM	✓	No corruption (800 kB)
MMCM	\checkmark	Jitter reduction of roughly 20%
PLL	✓	Jitter reduction of roughly 20%
IDELAYE2	\checkmark	Delay change of up to 30%
DSP48E1	✓	No corruption over 400 operations

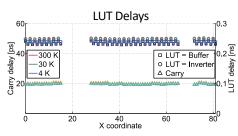
FPGA Performance

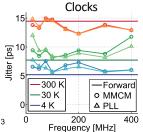
Specs:

Carry: 20 vs. 8.4 ps at 300 K LUTs: 238 vs 235 ps at 300 K

Speed-up 2.4 vs 10.8% toward 300 K

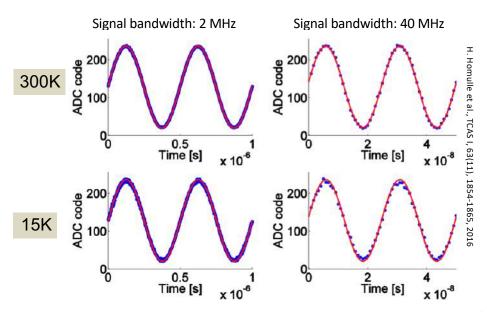




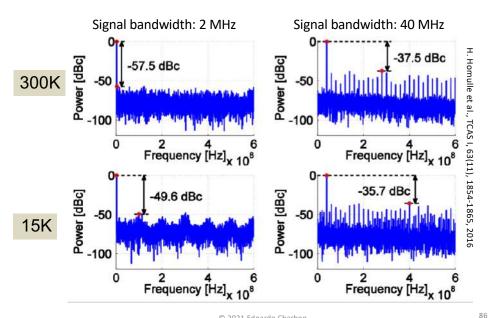




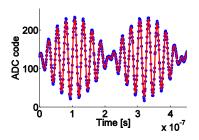
ADC on FPGA (1.2GSa/s)

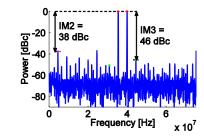


ADC on FPGA



- Two tones: ≈ 36 / 41 MHz
 - IM2 = 38 dB
 - IM3 = 46 dB
- Many secondary harmonics
- Interference with 100 MHz (sampling tone)

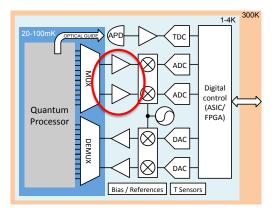


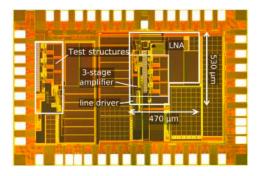


H. Homulle et al., TCAS I, 63(11), 1854-1865, 2016

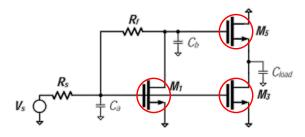


Low Noise Amplifiers (Cryo-LNAs)





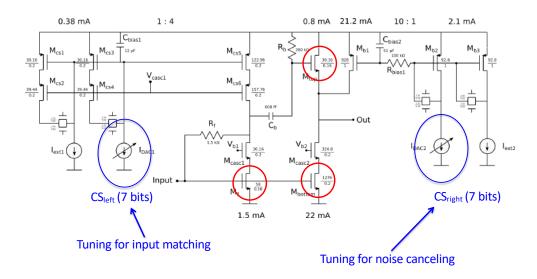
Cryo-LNA



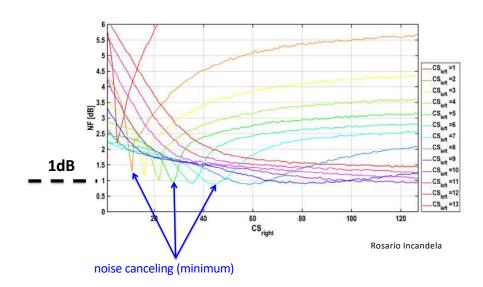
F. Bruccoleri et al., JSSC 2004

- Standard 160nm CMOS
- 500 MHz Bandwidth
- 0.1dB Noise figure
- 7K noise-equivalent temperature

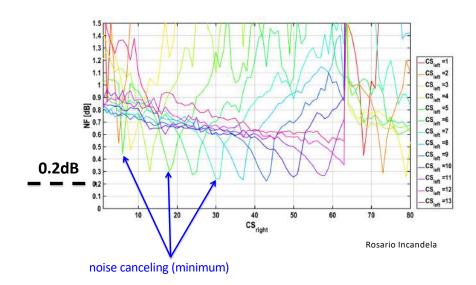
Cryo-LNA



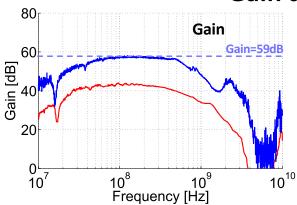
Noise Figure at RT



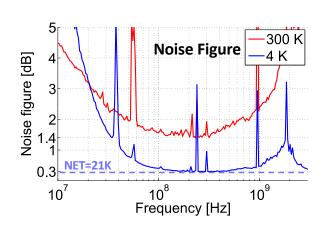
Noise Figure at 4K



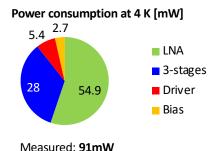
Gain and Noise

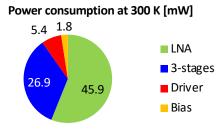


B. Patra, R. Incandela et al, JSSC 2018



Power





Measured: 80mW

Sharing 150x 1MHz-channels (one channel per qubit)

0.61mW per qubit

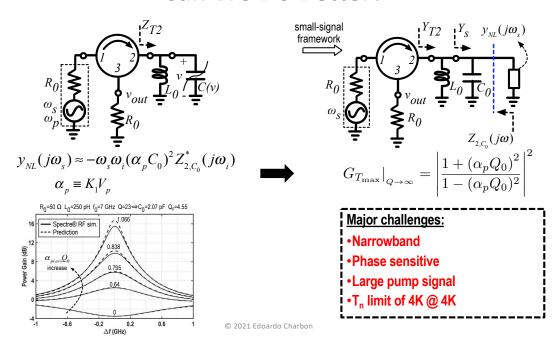
Rosario Incandela



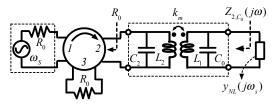
Can We Do Better?

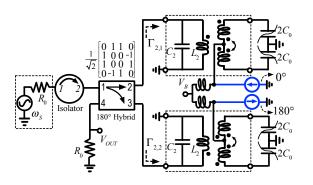
Amplifier Metrics	Cryogenic HEMT	JPA	TWPA 1.0	TWPA 2.0	
Power Dissipation	16 mW	100 pW	1 nW	5 nW	
Bandwidth (>15 dB gain)	11 GHz	100 - 200 MHz	6 GHz	5 GHz	
1-dB Compression point	0 dBm	-110 dBm (3 qubits)	-95 dBm (20-30 qubits)	-85 dBm (> 100 qubits)	
Noise Temperature	5 K	400 mK	400 mK	400 mK	
External Hardware	Isolator	Direct. Coupler, Circulator	Direct. Coupler	None	

Can We Do Better?



CMOS Parametric Amplifier



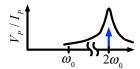


1) Transformer-based parametric amplifier

✓ Allow for broadband operation

2) CM impedance peaking

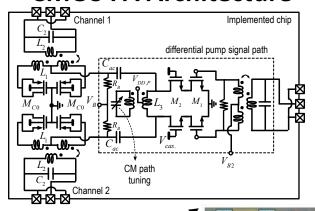
- ✓ Suppress the pump signal leak
- ✓ Reduce pump power consumption



3) "image"-rejection architecture

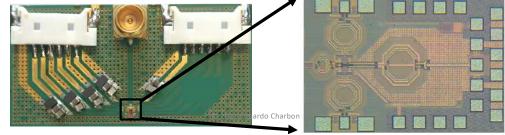
- ✓ Double the usable RF bandwidth.
- ✓ Phase-insensitive operation
- ✓ Allow for T_n limit of below 4K

CMOS PA Architecture

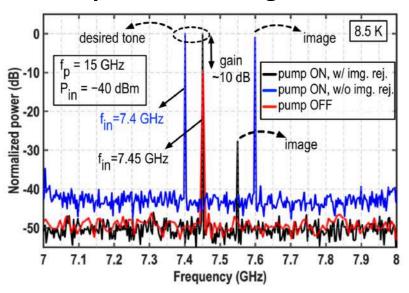


M. Mehrpoo, F. Sebastiano, E. Charbon, M. Babaie, *Solid-State Circuit Letters*, 2020

 $0.825 \ mm^2$

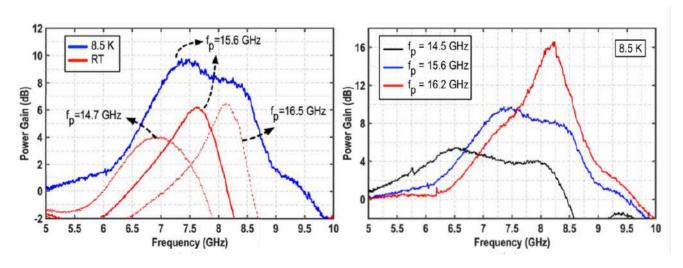


Spectrum of Single Tone



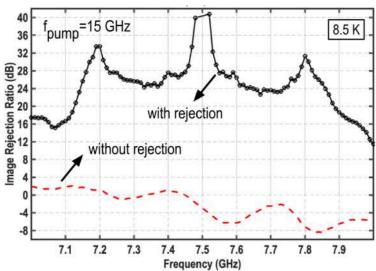
M. Mehrpoo, F. Sebastiano, E. Charbon, M. Babaie, Solid-State Circuit Letters, 2020

Power Gain vs. Pump Frequency and Temperature



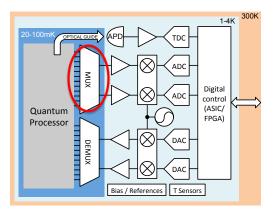
M. Mehrpoo, F. Sebastiano, E. Charbon, M. Babaie, Solid-State Circuit Letters, 2020

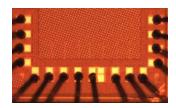
Image Rejection

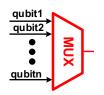


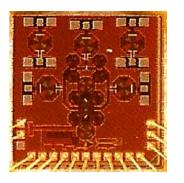
M. Mehrpoo, F. Sebastiano, E. Charbon, M. Babaie, Solid-State Circuit Letters, 2020

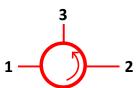
CMOS Passive Circulators & Multiplexers



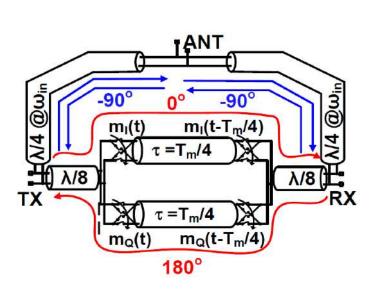


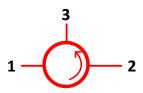






Transmission Line Circulator





S-parameters at ω_{in} = $3\omega_m$

$$S = \begin{bmatrix} 0 & 0 & -1 \\ -j & 0 & 0 \\ 0 & -j & 0 \end{bmatrix}$$

Passive Circulator Architecture

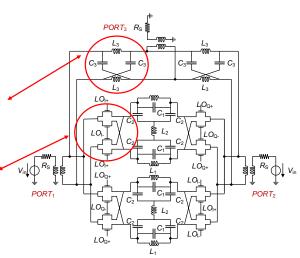
 Non-reciprocal behavior due to staggered commutation

Passive LC all-pass filters

 Passive mixers with nonoverlapping I/Q phases

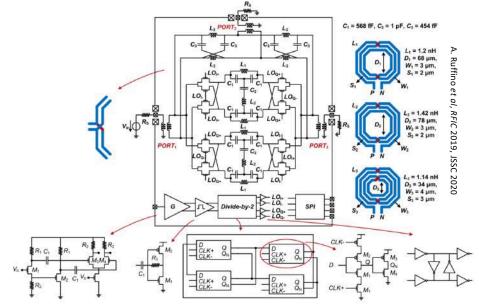
On-chip LO divider and I/Q generation

SPI control for tunability



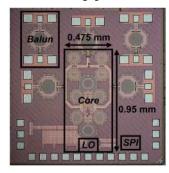
 $P_{DC} = 1.7 \text{ mW}$ $P_{AUX} = 8 \text{ mW}$

Passive Circulator Architecture

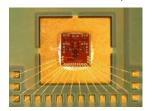


CMOS 40 nm Circulator Prototype

- TSMC CMOS 40 nm technology
- Tape-out, PCB design and measurements at 300 K and 4.2 K
- RF probing with LakeShore CPX probe station



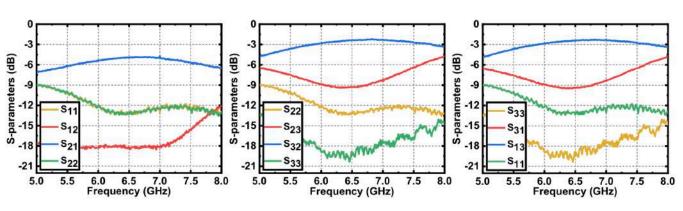
A. Ruffino et al, RFIC 2019, JSSC 2020





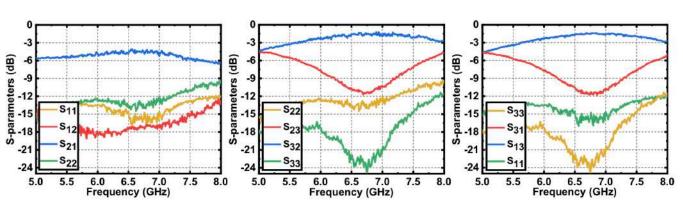


Measured S-parameters (300K)



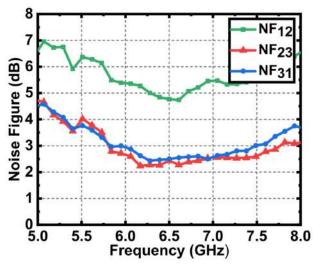
A. Ruffino et al, RFIC 2019, JSSC 2020

Measured S-parameters (4.2K)



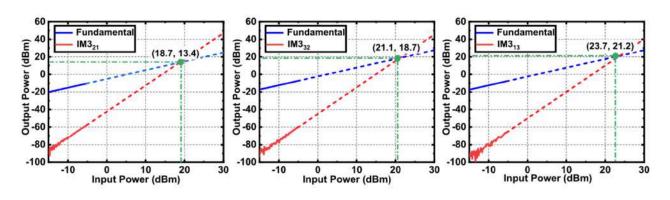
A. Ruffino et al, RFIC 2019, JSSC 2020

Circulator Noise Figure (300K)



Minimum noise figure of 2.1 dB is measured, consistent with insertion loss measurements. There is no excess noise from clock generation path.

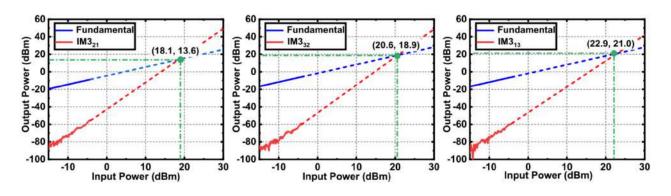
Circulator Linearity (300K)



A. Ruffino et al, RFIC 2019, JSSC 2020

High linearity is measured in all directions, due to the quasi-passive nature of the circulator.

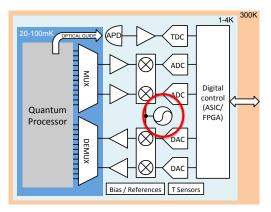
Circulator Linearity (4.2K)

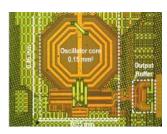


A. Ruffino et al, RFIC 2019, JSSC 2020

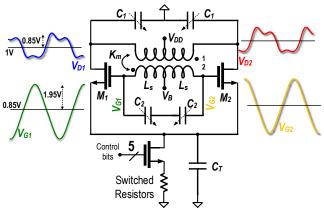
High linearity is measured in all directions, due to the quasi-passive nature of the circulator.

Cryo-Oscillators



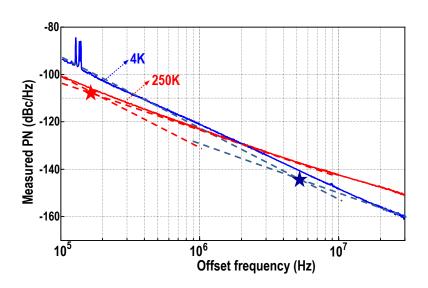


Cryo-Oscillator (Class F)

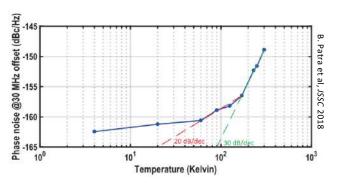


M. Shahmohammadi, ISSCC 2015

Phase Noise

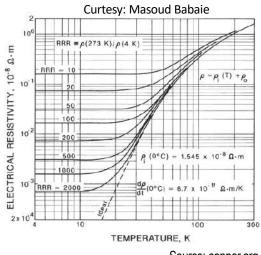


Measured Phase Noise



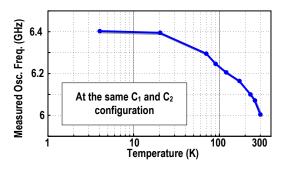
Sources of noise:

- Thermal noise
- Shot noise
- Impurities in copper



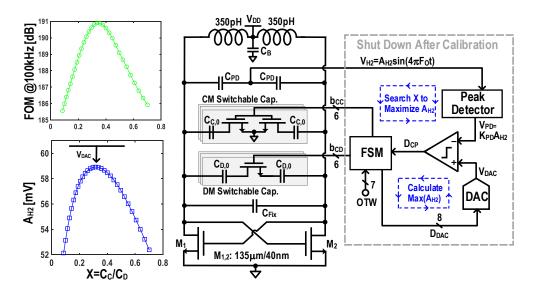
Source: copper.org

Frequency Stability

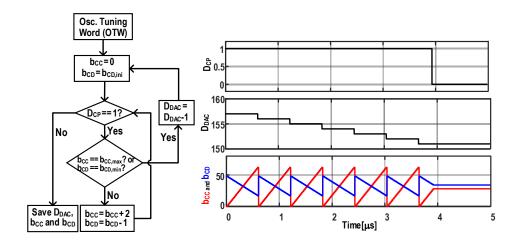


B. Patra et al, JSSC 2018

Improving Frequency Stability

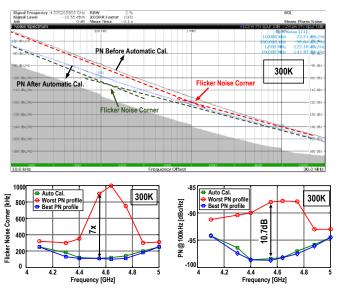


Improving Frequency Stability (2)



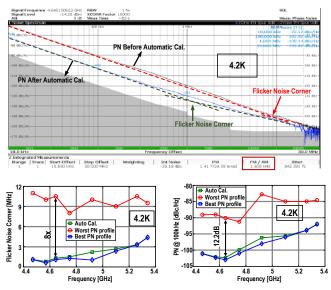
J. Gong, F. Sebastiano, E. Charbon, M. Babaie, ISSCC 2020

Phase Noise at 300K



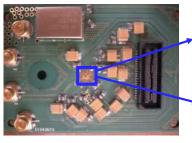
J. Gong, F. Sebastiano, E. Charbon, M. Babaie, ISSCC 2020

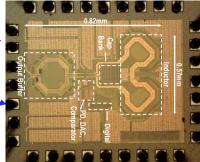
Phase Noise at 4K



J. Gong, F. Sebastiano, E. Charbon, M. Babaie, ISSCC 2020

Implementation in 40nm CMOS Node





Measurements at RT:

Technology: 40nm CMOS

F_{out}: 4.05-5.16GHz (24.1%)

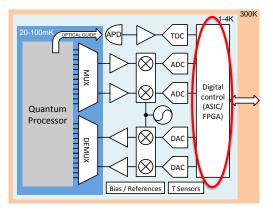
F_{ref}: 20MHz

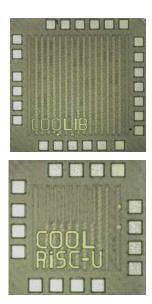
Supply: 0.5V (oscillator core) Power consumption: 3.2mW

PN @10MHz: -141.5dBc/Hz

PN@100kHz:-98.8dBc/Hz

Cryo-Logic





Ultra-Low Voltage Library 'cooLib'

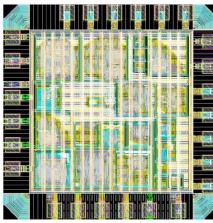
- Digital library optimized for 4K
- Ultra low voltage operation (100s mV)
- Sub-threshold bias of N/P MOS
- · Resilient to latchup and hysteresis-free
- Several logic families (static and dynamic CMOS)
- Compatible with commercial P&R tools

D-Flip-flop optimized for 4K (40nm CMOS)

12

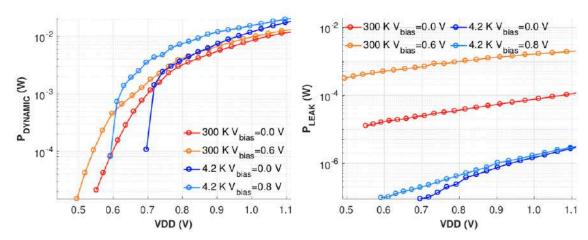
Test Chip Implementation

- Compare 'CooLib' cells to foundry supplied std. cells of TSMC40LP process
- Contains commonly encountered digital circuits
 - i.e. unsigned multiplier
- Four versions per circuit
 - Static 'CooLib'
 - Domino 'CooLib'
 - TSMC40LP, restricted
 - TSMC40LP, unrestricted
- One 'true' domino logic implementation

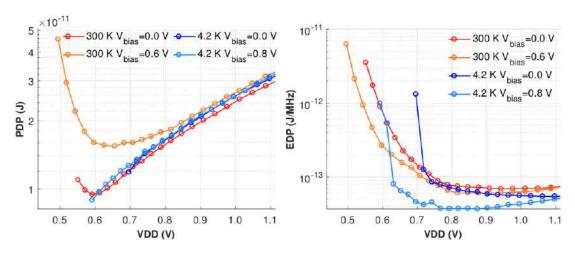


E. Schriek et al., IEEE Solid-State Circuits Letters 2020

Dynamic vs. Static Power at Cryo



FOMs



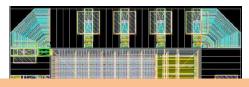
PDP: power-delay product EDP: energy-delay product

Benchmarking

Benchmark	Temp.	$V_{DD,MIN}$ [V]		$F_{MAX} @ 0.6 \text{ V [MHz]}$			$F_{MAX} @ 0.7 \text{ V [MHz]}$			P_{AVG} @ 100 kHz $[\mu W]$			
		Pro- posed	A	В	Pro- posed	A	В	Pro- posed	A	В	Pro- posed	A	В
16X16 Multiplier	4.2 K	0.54	0.68	0.68	16.3	(5)	S#3	74.2	4.6	2.0	2.34	3.76	3.88
	300 K	0.3	0.49	0.44	100.4	9.7	17.4	145.2	34.0	39.7	0.61	2.68	1.92
EPFL Sine	4.2 K	0.58	0.68	0.68	1.95	-		20.9	2.2	1.1	3.91	4.00	4.46
	300 K	0.39	0.34	0.39	15.2	9.2	9.5	29.6	25.5	26.4	3.46	2.11	2.18
EPFL Int- to-Float	4.2 K	0.54	0.68	0.68	51.4	(4)	1923	178.1	42.5	11.7	0.80	1.57	3.41
	300 K	0.24	0.38	0.36	118.5	75.2	73.44	174.2	191.9	158.0	0.08	0.55	0.28
EPFL Round- Robin Arbiter	4.2 K	0.58	0.68	0.68	21.6	(+)	-	46.6	2.0	1.8	7.89	11.56	11.64
	300 K	0.32	0.32	0.31	33.7	10.0	34.7	59.9	37.3	80.8	1.72	3.20	2.25

E. Schriek et al., IEEE Solid-State Circuits Letters 2020

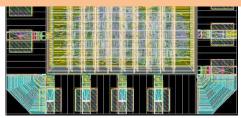
'CooLib' RISC-V Implementation



FEATURES

 RISC-V (picorv32, open-source) implemented using 'CooLib'

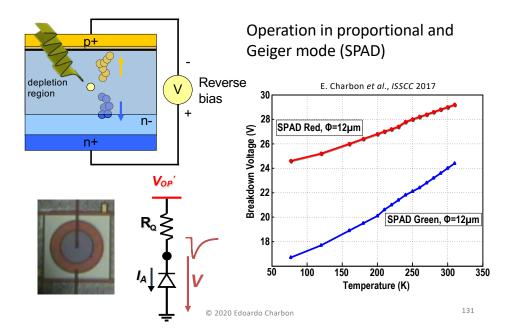
Fully functional μP operating at 4K



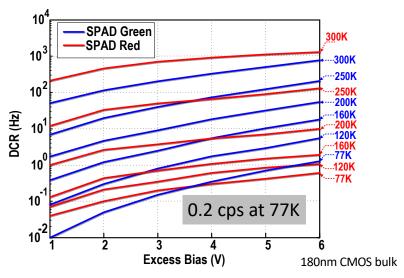
E. Schriek et al., IEEE Solid-State Circuits Letters 2020

- Interfacing by 'CooLib' level-shifters
- UART interface for serial in/output
- JTAG interface for SRAM write/read

Cryo-Single-Photon APDs (Cryo-SPADs)



Cryo-SPADs

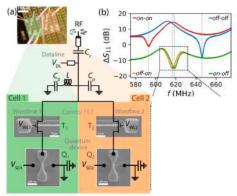


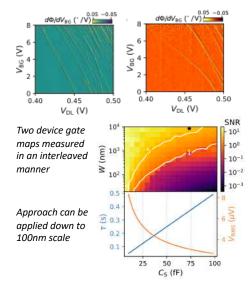
B. Patra et al., JSSC 2018

Qubits and Control in the Fridge



Step 1: Multiplexing Qubits









Step 2: Reading Qubits

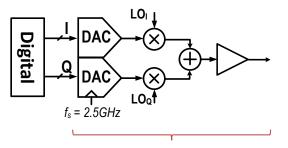
- Single-shot dispersive readout
- Single electron transistor readout
- · (limited) use of 3D stacking
- Ideally bring qubits to 1-4K, make them CMOS-compatible

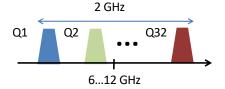
H. Homulle et al., QuRO interface Silicon Quantum Electronics Workshop, 2018



Step 3: Controlling Qubits

➤ Lower Speed DAC + Mixer





Analog: noise/linearity specifications known + feasible

Controlling Qubits: Specs

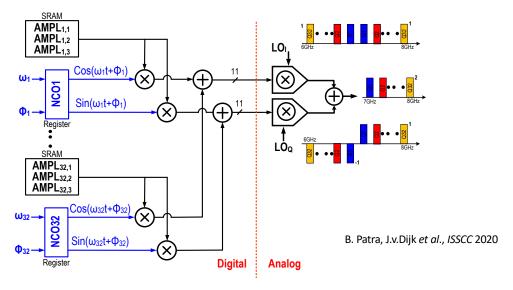
• Target fidelity: 99.99% for 1...10 MHz operation

Analog:

Error Source	Туре	Value	Contribution	
Microwave frequency	inaccuracy	35.4 kHz	1-F = 12.5 ppm	
(nominally 513 GHz)	noise	35.4 kHz _{rms}	1-F = 12.5 ppm	
Microwave phase	Inaccuracy	0.20 °	1-F = 12.5 ppm	
	noise	0.20 °	1-F = 12.5 ppm	
Microwave amplitude	inaccuracy	38.3 μV	1-F = 12.5 ppm	
(nominally 17 mV, -53 dB)	noise	38.3 μVrms	1-F = 12.5 ppm	
Microwave duration	inaccuracy	113 ps	1-F = 12.5 ppm	
(nominally 50 ns)	noise	113 psrms	1-F = 12.5 ppm	

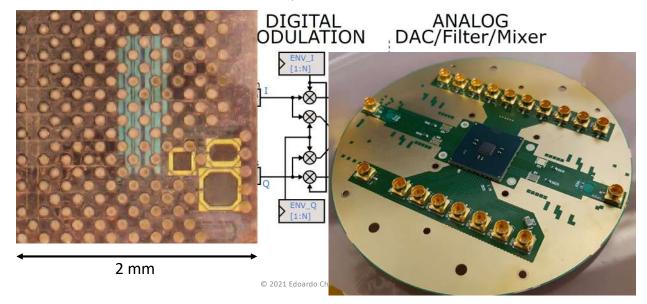
F = 99.99%

Controller Architecture: Horse Ridge

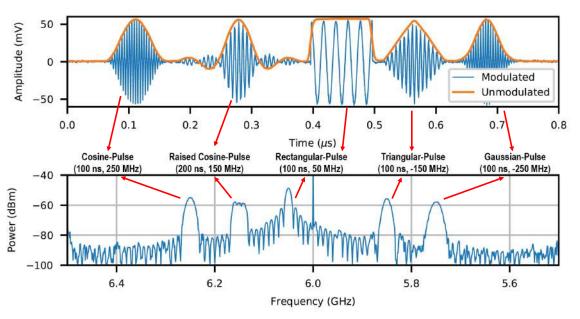


Controller Implementation

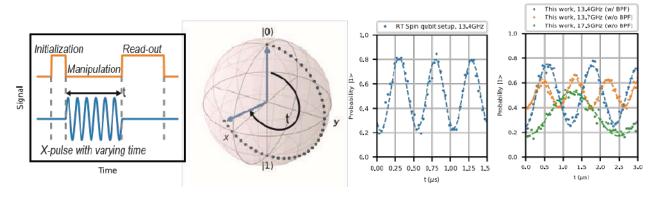
B. Patra, J.v.Dijk et al., ISSCC 2020



Pulse Shaping



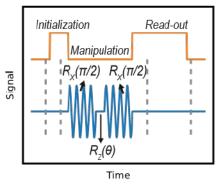
Rabi Experiment

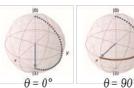


B. Patra, J.v.Dijk et al., ISSCC 2020

Qubit Manipulation





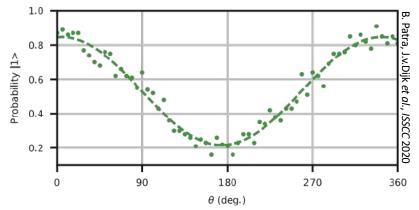










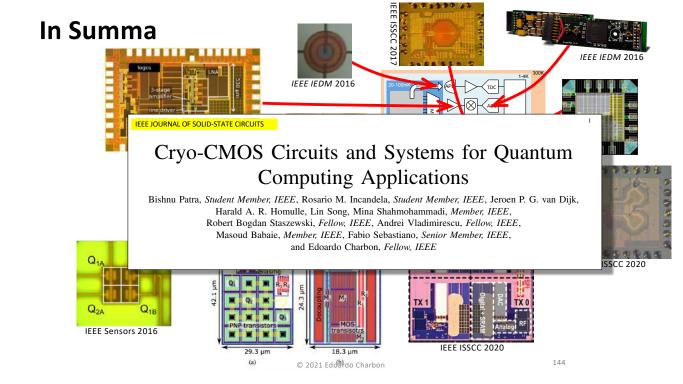


Comparison Table

	Horse Ridge (ISSCC'20)	ISSCC'19	RSI'17	Spin qubit setup
Operating Temperature	3 K	3 K	300 K	300 K
Qubit platform	Spin qubits + Transmons	Transmons	Transmons	Spin qubits
Qubit frequency	2 – 20 GHz	4 – 8 GHz		< 20 GHz
Channels	128 (32 per TX)	1	4	1
FDMA	Yes, SSB	No	Yes, SSB	No
Data Bandwidth	1 GHz	400 MHz	960 MHz	520 MHz
Image & LO leakage calibration	On chip	Off chip	Yes	
Phase correction	Yes	No	No	No
Fidelity (expected)	99.99%	-	-	-
Waveform/Instructions	Upto 40960 pts AWG	Fixed 22 pts symmetric		16M pts AWG
Instruction set	Yes	No	Yes	Yes
Power / TX	Analog: 1.7 mW/qubit * Digital: 330 mW ‡	Analog < 2 mW/qubit # Digital: N/A		850 W
Chip area / TX	4 mm ²	1.6 mm ²	Discrete	Rack mount
Technology	22 nm FinFET CMOS	28 nm bulk CMOS	components	

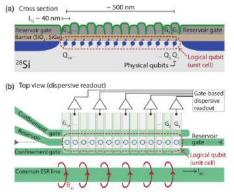
^{*} including LO/Clock driver; only RF-Low active # does not mention circuits included

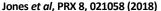
[‡] can be reduced with clock gating

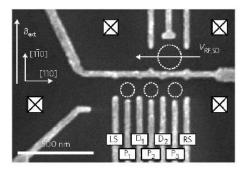


5. Conclusions

Realizations of 1D Qubit Arrangements



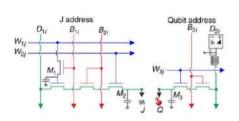


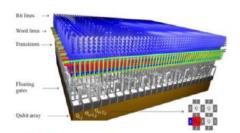


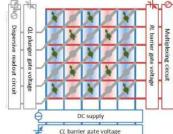
Baart et al, Nat Nano (2017)

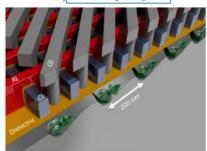
Proposals for Scalable Fault-Tolerant

2D Qubit Arrangements









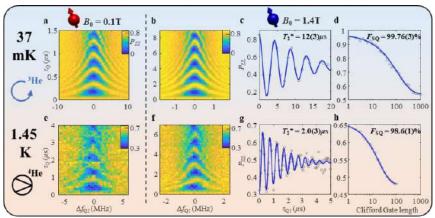
M. Veldhorst et al. (UNSW), Nature Comm. (2017)

R. Li et al., arXiv 1711.03807 (2017)

SiMOS QD Qubit Operation at 1.5 Kelvin

Silicon quantum processor unit cell operation above one Kelvin

C. H. Yang,^{1,*} R. C. C. Leon,¹ J. C. C. Hwang,^{1,†} A. Saraiva,¹ T. Tanttu,¹ W. Huang,¹ J. Camirand Lemyre,² K. W. Chan,^{1,‡} K. Y. Tan,^{1,‡} F. E. Hudson,¹ K. M. Itoh,³ A. Morello,¹ M. Pioro-Ladrière,^{2,4} A. Laucht,¹ and A. S. Dzurak^{1,§}



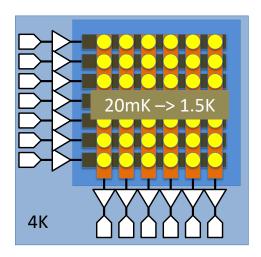
⇒ 1.5 K performance comparable to ^{nat}Si at 100 mK!

Courtesy: A. Dzurak



Platforms for the 2D Approach

- Single-shot dispersive readout could be the core of column readouts
- Use *imaging sensor* readout as inspiration
- Use tunneling barriers as selectors
- (limited) use of 3D stacking
- Ideally bring qubits to 1-4K, make them CMOS-compatible



Tradeoffs

1-qubit gate:

Oscillator phase noise Timing accuracy

...



<u>2-qubit gate:</u> Voltage drift Timing jitter ...



Power

(~ 1 mW/qubit)

Qubit read-out:

Amplitude noise

...

- Fidelity is usually expressed as a percentage, ofter referred to as x9's (e.g. 5 9's = 99.999%)
- Higher fidelity usually requires high power, which is budgeted, espcially at low temperatures (e.g. μW of thermal absorption at mK, while W at 4K)

Quantum Computing

- A quantum computer is a new computing paradigm and as such it holds the promise to handle today's intractable problems
- A qubit is fragile and thus needs to be constantly corrected to extend its coherence and to maintain fidelity
- Cryogenic electronics for quantum computing ensures compactness and scalability to much larger quantum processors

IceQubes: International Workshop on Cryogenic Electronics for Quantum Systems

June 2021, Neuchâtel - Switzerland

